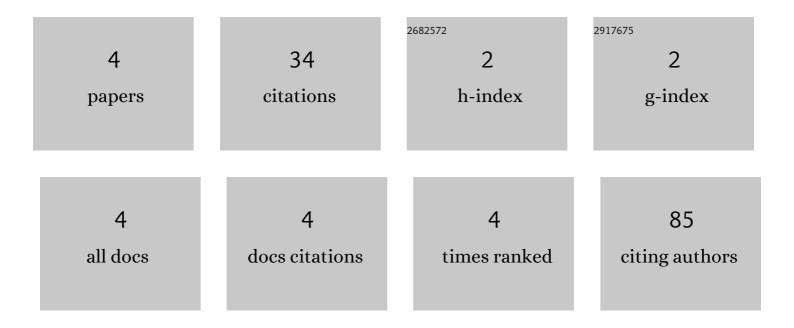
Chi-Feng Li

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/2881477/publications.pdf Version: 2024-02-01



#	Article	IF	CITATIONS
1	First demonstration of 40-nm channel length top-gate WS ₂ pFET using channel area-selective CVD growth directly on SiO _x /Si substrate. , 2019, , .		22
2	Experimentally Determining the Top and Edge Contact Resistivities of Two-Step Sulfurization Nb-Doped MoS2 Films Using the Transmission Line Measurement. IEEE Electron Device Letters, 2019, 40, 1662-1665.	3.9	7
3	Demonstration of 40-nm Channel Length Top-Gate p-MOSFET of WS ₂ Channel Directly Grown on SiO\$_{{x}}\$ /Si Substrates Using Area-Selective CVD Technology. IEEE Transactions on Electron Devices, 2019, 66, 5381-5386.	3.0	5
4	Comparison of Experimentally Extracted Top and Edge Contact Resistivity by TLM Structure with Two-step Sulfurization Nb-Doped MoS2. , 2019, , .		0